

WHAT IS CLAIMED IS:

1. A multilayer composite comprising:  
an insulating substrate; and  
patterned conductive layers and insulating layers alternately laminated on the insulating substrate to define a laminate; wherein  
at least one of the insulating layers defines a correcting insulating layer including vitreous silica and quartz;  
the ratio of vitreous silica to quartz in the correcting insulating layer is determined such that the thermal expansion coefficient of the correcting insulating layer differs from that of the insulating layers that do not define the correcting insulating layer, such that the correcting insulating layer corrects the warpage of the laminate attributed to a difference in thermal expansion coefficients between the insulating layers that do not define the correcting insulating layer, the patterned conductive layers, and the insulating substrate.
2. The multilayer composite according to claim 1, wherein at least a top layer of the laminate is the correcting insulating layer.
3. The multilayer composite according to claim 1, wherein the patterned conductive layers include a patterned photosensitive conductive paste.
4. The multilayer composite according to either claim 1, wherein at least one of the insulating layers has a via hole, at least two of the patterned conductive layers are connected through said via hole, and said at least one of the insulating layers is made of a patterned photosensitive insulating paste.
5. The multilayer composite according to either claim 1, wherein each of the insulating layers includes vitreous silica and quartz.

6. The multilayer composite according to either claim 1, wherein at least one of the insulating layers includes a via hole for connecting two of said patterned conductive layers.

7. A multilayer composite comprising:  
an insulating substrate; and  
patterned conductive layers and insulating layers alternately laminated on the insulating substrate so as to define a laminate; wherein  
each of the insulating layers includes vitreous silica and quartz;  
at least one of the insulating layers defines a correcting insulating layer;  
the ratio of vitreous silica to quartz in the correcting insulating layer differs from that in the other insulating layers such that the thermal expansion coefficient of the correcting insulating layer differs from that of the insulating layers that do not define the correcting insulating layer, such that the correcting insulating layer corrects the warpage of the laminate attributed to a difference in thermal expansion coefficient between the insulating layers that do not define the correcting insulating layer, the patterned conductive layers, and the insulating substrate.

8. The multilayer composite according to claim 7, wherein at least a top layer of the laminate is the correcting insulating layer.

9. The multilayer composite according to claim 7, wherein the patterned conductive layers are made of a patterned photosensitive conductive paste.

10. The multilayer composite according to either claim 7, wherein at least one of the insulating layers has a via hole, at least two of the patterned conductive layers are connected through said via hole, and said insulating layer is made of a patterned photosensitive insulating paste.

11. The multilayer composite according to either claim 7, wherein at least one of the insulating layers includes a via hole for connecting two of said patterned conductive layers.

12. A method for preparing a multilayer composite, comprising the steps of:  
alternately laminating patterned conductive layers and insulating layers on an insulating substrate to form a laminate;

forming at least one additional insulating layer having a different composition from that of the insulating layers to form a correcting insulating layer to correct the warpage of the laminate when a predetermined number of layers are laminated or when a predetermined degree of warpage of the laminate is detected by monitoring the laminating;  
and

laminating the correcting insulating layer on the laminate.

13. The method for preparing a multilayer composite according to claim 12, wherein at least a top layer of the laminate is the correcting insulating layer.

14. The method for preparing a multilayer composite according to claim 12, wherein the patterned conductive layers are formed by patterning a photosensitive conductive paste by photolithography.

15. The method for preparing a multilayer composite according to claim 12, wherein at least one of the insulating layers has a via hole, at least two of the patterned conductive layers are connected through said via hole, and said insulating layer is formed by patterning a photosensitive insulating paste by photolithography.

16. The method for preparing a multilayer composite according to claim 12, wherein each of the insulating layers includes vitreous silica and quartz.

17. The method for preparing a multilayer composite according to claim 12, further comprising the step of forming a via hole in at least one of the insulating layers so as to connect two of said patterned conductive layers through said via hole.